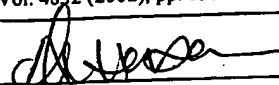


Form PTO-1449 (REV. 8-83)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 122800		APPLICATION NO. 10/525,372	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANTS Yasuhiro OMURA et al.			
				FILING DATE February 23, 2005			
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